CLAIM AMENDMENTS

Claims 1-13 (Canceled).

- 14. (Currently Amended) A substrate treatment—assembly apparatus comprising: a substrate heating device for maintaining a substrate at a temperature higher than room temperature;
- a wetting device for-obtaining producing a wet ozone-containing gas by wetting an ozone-containing gas with a treatment solution;
- a supply device for supplying-said the wet ozone-containing gas from the wetting device to a work object on a surface of said the substrate, said supply device comprising a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows;
- a gas conduit connecting said wetting device to said supply device; and a wet ozone-containing gas heating device for heating-said the wet ozone-containing gas-so as to-be at a temperature-approximately at least equal to-or greater than the temperature of-said the substrate.

Claim 15 (Canceled).

- 16. (Currently Amended) The substrate treatment assembly according to Claim 15 wherein spacing between adjacent rows of <u>aperture</u> apertures in said gas disperser is at least 5 mm-or more.
- 17. (Currently Amended) A substrate treatment-assembly apparatus for supplying an ozone-containing gas and a treatment solution to a work object on a surface of a substrate through, the assembly including a treatment agent supply plate-disposed facing-said the work object and through which the treatment solution is supplied, in which spacing between wherein a surface of-said the work object-and is spaced from said treatment agent supply plate-is by a distance in a range between 0.1 mm and 1.0 mm.